
**Surface chemical analysis —
Secondary ion mass spectrometry
— Calibration of the mass scale for
a time-of-flight secondary ion mass
spectrometer**

*Analyse chimique des surfaces — Spectrométrie de masse des ions
secondaires — Etalonnage de l'échelle de masse pour un spectromètre
de masse des ions secondaires à temps de vol*

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Foreword

ISO (the International Organization for Standardization) is a worldwide federation of national standards bodies (ISO member bodies). The work of preparing International Standards is normally carried out through ISO technical committees. Each member body interested in a subject for which a technical committee has been established has the right to be represented on that committee. International organizations, governmental and non-governmental, in liaison with ISO, also take part in the work. ISO collaborates closely with the International Electrotechnical Commission (IEC) on all matters of electrotechnical standardization.

The procedures used to develop this document and those intended for its further maintenance are described in the ISO/IEC Directives, Part 1. In particular, the different approval criteria needed for the different types of ISO documents should be noted. This document was drafted in accordance with the editorial rules of the ISO/IEC Directives, Part 2 (see www.iso.org/directives).

Attention is drawn to the possibility that some of the elements of this document may be the subject of patent rights. ISO shall not be held responsible for identifying any or all such patent rights. Details of any patent rights identified during the development of the document will be in the Introduction and/or on the ISO list of patent declarations received (see www.iso.org/patents).

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For an explanation of the voluntary nature of standards, the meaning of ISO specific terms and expressions related to conformity assessment, as well as information about ISO's adherence to the World Trade Organization (WTO) principles in the Technical Barriers to Trade (TBT) see www.iso.org/iso/foreword.html.

This document was prepared by Technical Committee ISO/TC 201, *Surface chemical analysis*, Subcommittee SC 6, *Secondary ion mass spectrometry*.

This second edition cancels and replaces the first edition (ISO 13084:2011), which has been technically revised.

The main changes to the previous edition are as follows:

- addition of [Annex B](#) (informative), *Internal addition method*.

Any feedback or questions on this document should be directed to the user's national standards body. A complete listing of these bodies can be found at www.iso.org/members.html.

Introduction

Secondary ion mass spectrometry (SIMS) is a powerful technique for the analysis of organic and molecular surfaces. Over the last decade, instrumentation has improved significantly so that modern instruments now have very high repeatability and constancy^[2]. An increasing requirement is for the identification of the chemical composition of complex molecules from accurate measurements of the mass of the secondary ions. The relative mass accuracy to do this and to distinguish between molecules that contain different chemical constituents, but are of the same nominal mass (rounded to the nearest integer mass), is thus an important parameter. A relative mass accuracy of better than 10 ppm is required to distinguish between C₂H₄ (28,031 30 u) and Si (27,976 92 u) in a parent ion with total mass up to 1 000 u, and between CH₂ (14,015 65 u) and N (14,003 07 u) in parent ions with total mass up to 300 u. However, in a recent interlaboratory study^[3], the average fractional mass accuracy was found to be 150 ppm. This is significantly worse than is required for unambiguous identification of ions. A detailed study^[4] shows that the key factors degrading the accuracy include the large kinetic energy distribution of secondary ions, non-optimized instrument parameters and extrapolation of the mass scale calibration.

This document describes a simple method, using locally sourced material, to optimize the instrumental parameters, as well as a procedure to ensure that accurate calibration of the mass scale is achieved within a selectable uncertainty.

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Surface chemical analysis — Secondary ion mass spectrometry — Calibration of the mass scale for a time-of-flight secondary ion mass spectrometer

1 Scope

This document specifies a method to optimize the mass calibration accuracy in time-of-flight secondary ion mass spectrometry (SIMS) instruments used for general analytical purposes. It is only applicable to time-of-flight instruments but is not restricted to any particular instrument design. Guidance is provided for some of the instrumental parameters that can be optimized using this procedure and the types of generic peaks suitable to calibrate the mass scale for optimum mass accuracy.

2 Normative references

There are no normative references in this document.

3 Terms and definitions

No terms and definitions are listed in this document.

ISO and IEC maintain terminological databases for use in standardization at the following addresses:

- ISO Online browsing platform: available at <https://www.iso.org/obp>
- IEC Electropedia: available at <http://www.electropedia.org/>

4 Symbols and abbreviated terms

4.1 Symbols

m	mass of interest
m_1	calibration mass 1
m_2	calibration mass 2
M	mass (u)
M_0	the peak centre (u)
ΔM	mass accuracy (u)
M_P	measured peak mass (u)
M_T	true mass (u)
$U(m)$	mass uncertainty for a mass, m , arising from calibration
U_1	uncertainty in the accurate mass measurement of m_1
U_2	uncertainty in the accurate mass measurement of m_2

U_0	average uncertainty in an accurate mass measurement
V_R	reflector or acceptance voltage (V)
W	relative mass accuracy
x	number of carbon atoms
y	number of hydrogen atoms
G_0	scaling term
α	asymmetry term
$\sigma(\Delta M)$	standard deviation of the mass accuracy for a number of peaks
σ_M	average of the standard deviations of ΔM for each of the four $C_xH_y^+$ cascades with 4, 6, 7 and 8 carbon atoms

4.2 Abbreviated terms

MEMS	micro-electromechanical system
PC	polycarbonate
ppm	parts per million
r/min	revolutions per minute
SIMS	secondary ion mass spectrometry
THF	tetrahydrofuran
ToF	time-of-flight

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5 Outline of method

Here, the method is outlined so that the detailed procedure, given in [Clause 6](#), may be understood in context. Firstly, to optimize a time-of-flight mass spectrometer using this procedure, obtain a thin film of polycarbonate (PC) on a conducting substrate (silicon). The optimization procedure is achieved by carrying out the procedures in [6.3](#) to [6.5](#) iteratively; it uses 19 specific C_xH_y peaks in the PC positive-ion mass spectrum. In [6.6](#), a general calibration procedure is given which provides the rules by which calibrations for inorganics and organics may be incorporated. This leads to a new generic set of ions for mass calibration that can improve the mass accuracy from some often-used calibrations by a factor of five. The effects of extrapolation beyond the calibration range are discussed and a recommended procedure is given to ensure that accurate mass is achieved, within a selectable uncertainty, for large molecules. Therefore, the procedure has two parts, optimization and calibration. [6.1](#) to [6.5](#) are only required as part of the regular maintenance of the instrument as defined by the testing laboratory. [6.6](#) is required for all calibrations of the mass scale. This is summarized in the flowchart in [Figure 1](#).

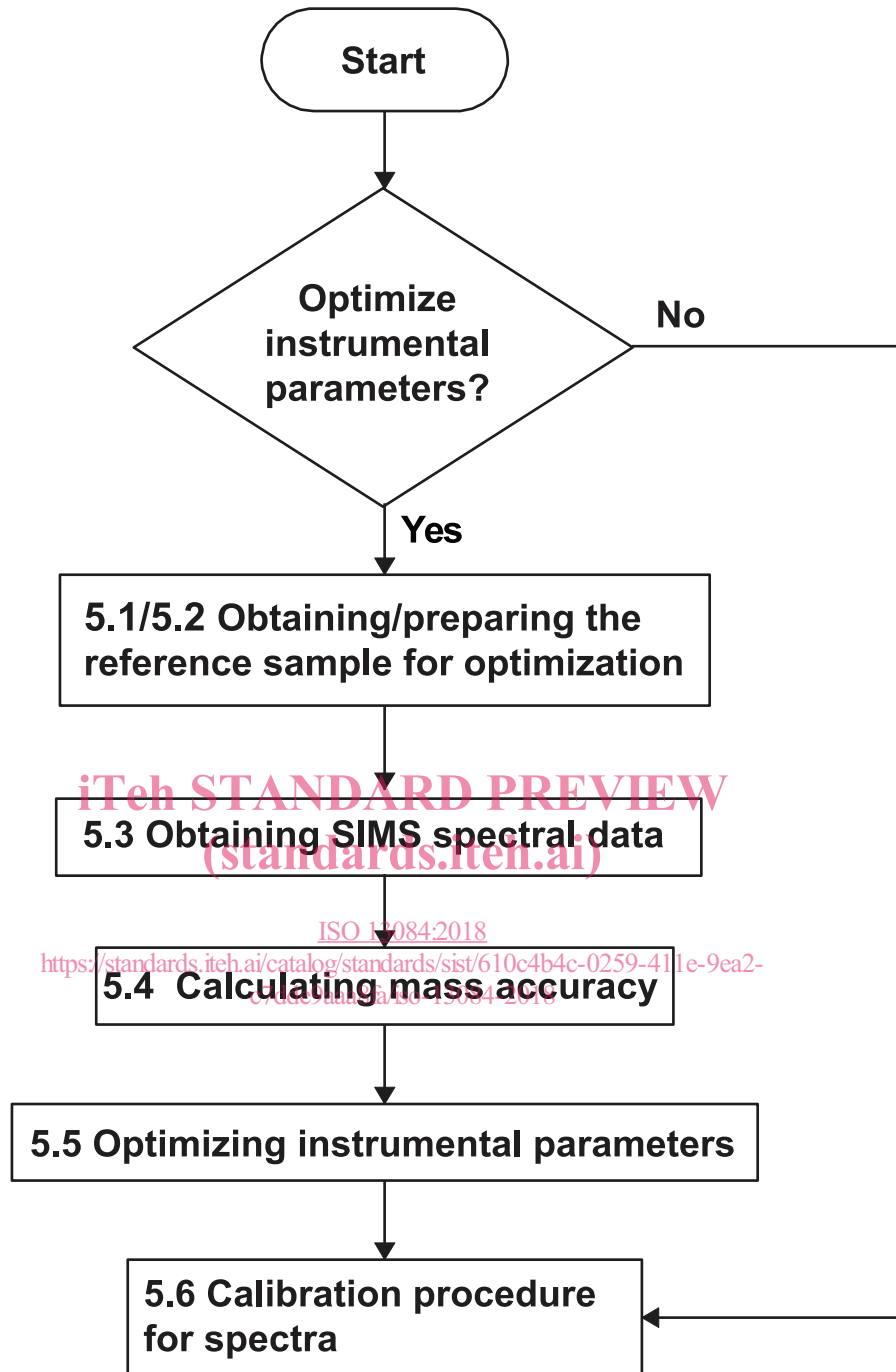


Figure 1 — Flowchart of sequence of operations of the method

6 Method for improving mass accuracy

6.1 Obtaining the reference sample for optimization

A sample of thin (10 to 100 nm) PC on a flat conducting substrate (e.g. silicon wafer) shall either be obtained or prepared, as described in 6.2.

6.2 Preparation of polycarbonate sample

6.2.1 Instructions for the preparation of a PC reference sample are provided. This method can give sample-to-sample repeatability in ToF SIMS spectra of better than 1,9 %^[2]. To prepare such a sample for static SIMS analysis requires a clean working environment. To reduce surface contamination, clean glassware, tweezers and powderless gloves shall be used. The equipment required is a 1 ml glass pipette, a 100 ml glass-stoppered measuring flask and a device for spin casting. If a device for spin casting is not available, droplet deposition of the PC solution may be used. However, this will give poor repeatability, which will need to be carefully taken into account during spectral analysis.

6.2.2 Using poly(bisphenol A carbonate), abbreviated to PC, weigh out 100 mg on a clean piece of aluminium foil. Introduce the PC into the 100 ml, glass-stoppered measuring flask, add tetrahydrofuran (THF) of analytical reagent quality to the 100 ml level line. Shake the flask to mix the PC and allow time to dissolve it completely. This produces a 1 mg/ml solution of PC in THF. The aluminium foil shall be freshly unrolled and the shiny surface used. Ensure that the THF is anhydrous, otherwise streaks will appear from water when spin coating, as described in 6.2.3. The shelf life of freshly prepared stock solution shall be no more than one month owing to water take-up.

NOTE 1 It does not matter if the PC contains low levels of additives.

NOTE 2 It does not matter if the final PC/THF solution concentration varies by ± 20 %.

6.2.3 Use a conveniently sized (1 cm by 1 cm) piece of silicon, or another flat or polished conducting substrate, and clean it overnight by soaking in propan-2-ol (isopropyl alcohol). Ultrasonically clean the substrate in fresh propan-2-ol and dry. If an ultrasonic bath is not available, just rinse the sample in fresh propan-2-ol. Mount the substrate on the spin casting device. Pipette approximately 0,2 ml of the PC solution onto the substrate and spin cast at 4 000 r/min for 25 s. Samples may be prepared by depositing the PC solution using a 5 ml pipette onto the silicon surface then air drying under ambient conditions. However, this method will result in an uneven PC film, so care shall be taken when comparing spectra, as peak intensities will vary. <https://standards.iteh.ai/catalog/standards/sist/610c4b4c-0259-411e-9ea2-c7dde9aaa8fa/iso-13084-2018>

NOTE 1 It is not essential what substrate is used, as long as it is conducting. Silicon has been found to give good-quality films.

NOTE 2 Using this procedure, the film thickness will be approximately 10 nm. The absolute thickness is not critical. However, if it is too thick, the optimal SIMS spectral data might not be obtained due to the charge build up (charging).

6.3 Obtaining the SIMS spectral data

6.3.1 Insert the PC sample inside the chamber of the SIMS instrument.

6.3.2 Operate the instrument in accordance with the manufacturer's or local documented instructions. The instrument shall have fully cooled following any bakeout. Ensure that the operation is within the manufacturer's recommended ranges for the ion-beam current, counting rates and any other parameter specified by the manufacturer. Check that the detector multiplier settings are correctly adjusted.

6.3.3 Select the normal analytical settings and acquisition time. For ToF instruments, select a repetition rate that gives a maximum mass of at least 800 u. If the total counts in the $C_9H_{11}O^-$ peak are less than 10 000, increase the acquisition time to ensure that this peak contains more than 10 000 counts. This may not be possible if the signal is too weak and it is not possible to achieve 10 000 counts within a reasonable time. To ensure that the maximum ion fluence (1×10^{16} ions/m²) is not exceeded, an enlarged raster area may be required. The acquisition time finally chosen will be a compromise between the data quality and the duration of the work. Record the parameters set. Ensure that the detector is not saturated using the manufacturer's or local documented instructions. This may be achieved by reducing the number of primary ions per pulse.

NOTE For details of acquiring high-quality SIMS spectra with good repeatability and constancy, refer to ISO 23830[4].

6.4 Calculating mass accuracy

6.4.1 Instrument manufacturers' software may provide the calculation of the peak position automatically; it is often sufficient to use this to obtain a value of M_0 . A more accurate and reliable method for measurement of the mass of the peak in the spectra, M_0 , can be used. An asymmetric Gaussian function, G_A , can be used to fit to the signal intensity versus the mass position, M_P , and the fitting used to calculate the peak position, M_0 , where M_0 is the peak centre, M_P is the peak mass and G_0 is a scaling term. G_A , the fit to signal intensity, is given by [Formulae \(1\)](#) and [\(2\)](#):

$$G_A = G_0 \exp\left(\frac{-(M_P - M_0)^2}{2[\sigma - \alpha(M_P - M_0)]^2}\right) \quad (1)$$

and

$$\sigma = \frac{\text{FWHM}(\alpha = 0)}{2\sqrt{2\ln 2}} \quad (2)$$

where $\text{FWHM}(\alpha = 0)$ is the full width at half-maximum of the base Gaussian width for $\alpha = 0$. The term α gives the asymmetry, and for $\alpha = 0$ the function is pure Gaussian.

For each peak, fit [Formula \(1\)](#). Only use those intensities above 50 % of the maximum intensity to avoid interference from neighbouring peaks. You should calibrate using the peak position method you intend to use for accurate mass identification in your work.

NOTE An asymmetric Gaussian function gives a good fit to a wide range of peak shapes, whereas the mean value can lead to significant errors for asymmetric peaks. Typically, the asymmetric Gaussian function is an excellent description of the peak down to 15 % of the maximum intensity, although the fitting, here, only covers to 50 %.

6.4.2 The mass accuracy, ΔM , is defined as the difference between the measured peak mass, M_P , and the true mass, M_T , as shown in [Formula \(3\)](#).

$$\Delta M = M_P - M_T \quad (3)$$

The relative mass accuracy, W , is given in [Formula \(4\)](#).

$$W = \frac{\Delta M}{M_T} \quad (4)$$

In the text that follows, W will be given in parts per million.

6.4.3 [Figure 2](#) shows ΔM for a range of hydrocarbon peaks of polycarbonate in an unoptimized instrument. ΔM varies widely along the mass range for ions with different fragmentation. This illustrates an instrument with modest mass scale accuracy.

In [Figure 2](#) the peaks marked with an arrow are used to calibrate the spectra. The circumscribed symbols denote the mass peaks used to measure σ_M . Here the asymmetric Gaussian function is used.